

Special Issue

New Technologies and Processing of Photoelectric Functional Materials and Devices

Message from the Guest Editors

This Special Issue on “New Technologies and Processing of Photoelectric Functional Materials and Devices” seeks high-quality works focusing on the latest functional materials for photoelectrical devices. Topics include, but are not limited to:

- Perovskite materials;
- Low-dimensional materials and heterostructures;
- Organic materials;
- Quantum dots;
- Light-emitting diodes (LEDs);
- Photodetectors;
- Photovoltaic devices.

Guest Editors

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Dr. Wei Zhang

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Deadline for manuscript submissions

closed (31 July 2025)



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Editor-in-Chief

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